L Number	Hits	Search Text	T DD	
2	9011		DB USPAT;	Time stamp
		216/67.ccls. 134/1.2.ccls.	US-PGPUB;	2004/08/11 14:45
			EPO; JPO;	
_			DERWENT	1
3	751235	resist photoresist photo-resist	USPAT;	2004/08/11 14:46
		photosensitive photo-sensitive (sensitive	US-PGPUB;	, , , , , , , , , , , , , , , , , , , ,
		near (photo light energy radiation))	EPO; JPO;	
4	437966	/	DERWENT	
3	43/900	(organic polymer polymeric resin) near	USPAT;	2004/08/11 14:46
		(layer underlayer under-layer film coating)	US-PGPUB;	
			EPO; JPO;	
5	608	treat\$3 near3 plasma near3 (ethylene	DERWENT	0001/00/00
		hydrogen h2 "h.sub.2" c2h4 "c.sub.2	USPAT;	2004/08/11 14:46
		h.sub.4")	US-PGPUB;	,
		,	EPO; JPO; DERWENT	
7	41234	plasma near3 (reduc\$3 chemical\$3)	USPAT;	2004/08/11 15:04
		, ,	US-PGPUB;	2001/00/11 15:04
			EPO; JPO;	
	~ -	MANOROUS	DERWENT	
1	31		USPAT;	2004/08/11 14:49
		MAHOROWALA-ARPAN-PRAVINin.	US-PGPUB;	li-
		MAHOROWALA-A-Pin. MAHOROWARAin.	EPO; JPO;	}
9	1397	(430/311,313,314,316,317.ccls. 438/710.ccls.	DERWENT	
	233.	216/67.ccls. 134/1.2.ccls.) and ((treat\$3	USPAT;	2004/08/11 14:52
		near3 plasma near3 (ethylene hydrogen h2	US-PGPUB; EPO; JPO;	
		"h.sub.2" c2h4 "c.sub.2 h.sub.4")) (plasma	DERWENT	
		near3 (chemical\$2-reduc\$3 chemical\$2 near	BERNENT	
]]		reduc\$3)) (plasma near3 (reduc\$3 chemical\$3)		
))		
6	32	plasma near3 (chemical\$2-reduc\$3 chemical\$2	USPAT;	2004/08/11 15:03
		near reduc\$3)	US-PGPUB;	
			EPO; JPO;	
11	112	(resist photoresist photo-resist	DERWENT	
		photosensitive photo-sensitive (sensitive	USPAT;	2004/08/11 15:05
		near (photo light energy radiation))) same	US-PGPUB;	
		((organic polymer polymeric resin) near	EPO; JPO; DERWENT	
		(layer underlayer under-layer film coating)	PEKMENI	
	1) same ((treat\$3 near3 plasma near3		
		(ethylene hydrogen h2 "h.sub.2" c2h4		
		"c.sub.2 h.sub.4")) (plasma near3 (reduc\$3]	
12	10070	chemical\$3)))		
14	12972	plasma near3 (reduc\$3)	USPAT;	2004/08/11 15:04
	İ		US-PGPUB;	
	ŀ		EPO; JPO;	
13	19	(resist photoresist photo-resist	DERWENT	
		photosensitive photo-sensitive (sensitive	USPAT;	2004/08/11 15:05
		near (photo light energy radiation))) same	US-PGPUB;	
		((organic polymer polymeric resin) near	EPO; JPO; DERWENT	
		(layer underlayer under-layer film coating)	DUMBIAT	
) same ((plasma near3 (reduc\$3)))		
				I